



FOCUS TECH *Process Chemicals*

Technical Data Sheet

Focus Tech FS-79/OL

Semi-Aqueous Photoresist Stripper

Product Description

FS-79/OL is a semi-aqueous photoresist stripper concentrate formulated specifically to strip dry film from between very fine lines and underneath overplated features. FS-79/OL combines alkaline amines with glycol ethers to provide the absolutely smallest dry film particles over the entire loading range of the process. FS-79/OL strips quickly and leaves the copper surface clean and free of oxidation. FS-79/OL is designed to completely remove the tenacious adhesion promoters used in many of today's photoresists.

Physical Properties

Specific gravity: 1.0
pH: > 13
Appearance: clear, water white to light amber liquid
Flash point: > 200 °F

Operating Parameters

Concentration: 5 - 20% v/v
Temperature: 120 – 140 °F

Storage

Store in original containers above 40 °F.

Safety

CAUTION! FS-79/OL concentrates and working solutions contain strong alkaline ingredients. Avoid contact with eyes, skin and clothing. Wear chemical handler's gloves, goggles and protective clothing when handling. Read and understand Material Safety Data Sheet before using this product.

Notice

The information and recommendations, contained herein, regarding this product are, to the best of our knowledge, true and accurate. We make no guarantee of results because the conditions of actual use are beyond our control. We assume no liability for damages or penalties resulting from the use of this product or following our recommendations. Our recommendations and suggestions for use of this product are not intended to grant license to operate under or infringe any patent.